

Materials List for:

Atomically Traceable Nanostructure Fabrication

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Materials

Name	Company	Catalog Number	Comments
Si Wafer	VA Semiconductor		P type (Boron) Si<100> ± 2 degrees, 280 mm ± 25 mm thick, 0.01-0.02 ohm-cm
Ta foil	Alfa Aesar	335	0.025 mm (0.001 in) thick, 99.997% (metals basis)
Methanol	Alfa Aesar	19393	Semiconductor Grade, 99.9%
2-Propanol	Alfa Aesar	19397	Semiconductor Grade, 99.5%
Acetone	Alfa Aesar	19392	Semiconductor Grade, 99.5%
Argon	Praxair		Ultra high purity (grade 5.0)
Deionized water	Millipore	Milli-Q Water Purification System	>18 MW resistance water produced on demand.
TiCl ₄	Sigma Aldrich	254312	≥99.995% trace metals basis
O ₂	Matheson	G2182101	Research Grade
SF ₆	Matheson	G2658922	Ultra high purity (grade 4.7)
Blue Medium Tack Roll	Semiconductor Equipment Corporation	18074	Thickness 75 µm / 0.003" Length 200 M / 660'